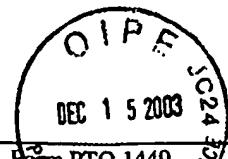




Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include a copy of this form with the next communication to applicant.

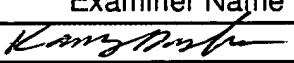


Information Disclosure Statement by Applicant					Att. Docket No. ACT-377		Serial No. 10/625,490	
(Use several sheets if necessary)					Filed: July 22, 2003		Group: Not yet assigned	
U.S. Patent Documents								
Init.		Document No.	Date	Name	Class	Subclass	Filing Date	
<i>(A large grid for listing U.S. Patent Documents, with a diagonal line drawn through it.)</i>								
Foreign Documents								
Translation								
Init.		Document No.	Date	Country	Class	Subclass	Yes	No
<i>DHIC</i>	22	JP 60-242678 A Eng. Lang. Abst.	12/02/1985	Japan	H01L	29/78		X
	23	EP 0 250 078 A2	12/23/1987	Europe	H01L	23/52		X
	24	WO 92/21154	11/26/1992	PCT	H01L	45/00		X
	25	JP 06-295991 A Eng. Lang. Abst.	10/21/1994	Japan	H01L	27/10		X
	26	EP 0 671 767 A2	09/13/1995	Europe	H01L	23/525		X
	27	EP 0 671 767 A3	01/21/1998	Europe	H01L	23/525		X
<i>(A large grid for listing Foreign Documents, with a diagonal line drawn through it.)</i>								
Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)								
<i>DHIC</i>	28	S. Liu et al., "A New Metal-to-Metal Antifuse with Amorphous Carbon", <u>IEEE Electron Device Letters</u> , Vol. 19, No. 9, September 1998.						
<i>DHIC</i>	29	"High Purity Carbon and Graphite Products", Toshiba Ceramics, [Internet] http://tocera.co.jp/en/products/semi/carbon.html , pp. 1-2, copyright 1999, printed on October 9, 2003.						
Examiner <i>Kang, Donghee</i>					Date Considered <i>08-05-05</i>			
Examiner: Initial if citation considered, whether or not citation is in conference with MPEP 609; Draw line through citation if not conformance and not considered. Include a copy of this form with the next communication to applicant.								

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	SWITCHING RATIO AND ON STATE RESISTANCE OF AN ANTIFUSE PROGRAMMED BELOW 5 mA AND HAVING A Ta or TaN BARRIER METAL LAYER							
Application Number :	10/625490							
Confirmation Number:	9116							
First Named Applicant:	A Farid Issaq							
Attorney Docket Number:								
Art Unit:								
Examiner:								
Search string:	(4599705 or 5008855 or 5126282 or 6583953).pn							
US Patent Documents								
Note: Applicant is not required to submit a paper copy of cited US Patent Documents								
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass	
ONH	1	4599705	1986-07-08	Holmberg et al	A	365	163	
	2	5008855	1991-04-16	Eltoukhy et al	A	365	96	
	3	5126282	1992-06-30	Chiang et al	A	437	172	
	4	6583953	2003-06-24	Han et al	A	360	122	
Signature								
Examiner Name				Date				
				08-05-05				

